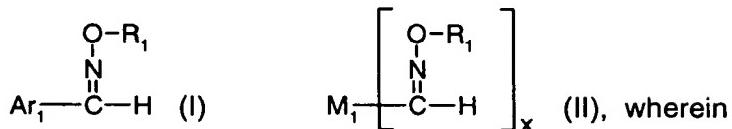


Abstract

Photosensitive compositions comprising

- (A) an alkali soluble compound;  
(B) at least one compound of formula I or II



R<sub>1</sub> inter alia is C<sub>4</sub>-C<sub>9</sub>cycloalkanoyl, C<sub>3</sub>-C<sub>12</sub>alkenoyl, or benzoyl which is unsubstituted or substituted; Ar<sub>1</sub> is either C<sub>6</sub>-C<sub>20</sub>aryl or C<sub>6</sub>-C<sub>20</sub>aryloyl each of which is unsubstituted or substituted; x is 2 or 3; M<sub>1</sub> when x is 2, inter alia is a group phenylene or naphthylene, each of which optionally is substituted i.a. by OR<sub>3</sub>, SR<sub>4</sub> or NR<sub>5</sub>R<sub>6</sub>; or M<sub>1</sub>, when x is 3, is a trivalent group, optionally substituted; R<sub>3</sub> is for example hydrogen or C<sub>1</sub>-C<sub>12</sub>alkyl; C<sub>2</sub>-C<sub>6</sub>alkyl which is for example substituted by -OH, -SH, -CN, C<sub>3</sub>-C<sub>6</sub>alkenoxy, or -OCH<sub>2</sub>CH<sub>2</sub>CN; R<sub>4</sub> is for example hydrogen, C<sub>1</sub>-C<sub>12</sub>alkyl, C<sub>3</sub>-C<sub>12</sub>alkenyl, cyclohexyl, or phenyl which is unsubstituted or substituted; R<sub>5</sub> and R<sub>6</sub> independently of each other inter alia are hydrogen, C<sub>1</sub>-C<sub>12</sub>alkyl, C<sub>2</sub>-C<sub>4</sub>hydroxyalkyl, C<sub>2</sub>-C<sub>10</sub>alkoxyalkyl, C<sub>3</sub>-C<sub>5</sub>alkenyl, C<sub>3</sub>-C<sub>8</sub>cycloalkyl, phenyl-C<sub>1</sub>-C<sub>3</sub>alkyl, C<sub>1</sub>-C<sub>4</sub>alkanoyl, C<sub>3</sub>-C<sub>6</sub>alkenoyl, benzoyl or phenyl which is unsubstituted or substituted; and  
(C) a photopolymerizable compound;

exhibit an unexpectedly good performance, in particular in photoresist technology.